



### Radiation Effects on Emerging Electronic Materials and Devices

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### The Commons











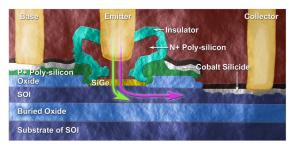


### Radiation Effects in Emerging Electronic Materials and Devices



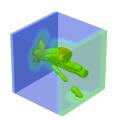
#### **Motivation**

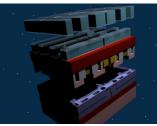
 More changes in IC technology and materials in past five years than previous forty years—impact on radiation response is dramatic



#### **Selected Results**

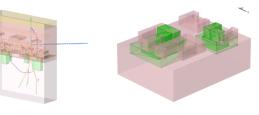
- · Development of most accurate rate-prediction tool to date
- · Identification of tungsten as key rad-effects issue
- Fabrication of rad-hard, reliable alternative gate dielectrics
- Demonstration of extremely rad-hard SiGe technology
- First examination of rad effects in strained-Si CMOS





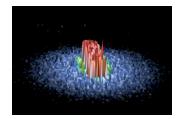
#### Approach

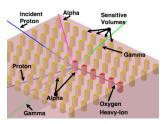
- Experimental analysis of state-of-the-art technologies through partnerships with semiconductor manufacturers
- Identification of critical mechanisms through firstprinciples modeling
- Implementation and application of a revolutionary multiscale radiation-effects simulation tool to identify key challenges and develop hardening approaches



#### Impact

- Design tools and methods demonstrated for future radhard technologies
- Greatly improved error-rate analysis tools allow implementation of more reliable space electronics
- First radiation-effects characterization of most advanced technologies (strained Si, HfSiON, etc.)—essential for deployment of state-of-the-art electronics in DoD systems







### **Team Members**



- Vanderbilt University
  - Electrical Engineering: Mike Alles, Dan Fleetwood, Ken Galloway, Marcus Mendenhall, Lloyd Massengill, Robert Reed, Ron Schrimpf, Bob Weller
  - Physics: Len Feldman, Sok Pantelides
- Arizona State University
  - Electrical Engineering: Hugh Barnaby
- University of Florida
  - Electrical and Computer Engineering: Mark Law, Scott Thompson
- Georgia Tech
  - Electrical and Computer Engineering: John Cressler
- North Carolina State University
  - Physics: Gerry Lucovsky
- Rutgers University
  - Chemistry: Eric Garfunkel, Gennadi Bersuker
- Industrial and government collaborators
  - IBM, Intel, Texas Instruments, Freescale, Jazz, National Semiconductor, SRC/Sematech, Sandia, NASA/DTRA, Lockheed-Martin, Oak Ridge National Lab, CFDRC

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Resource to support national requirements in radiation effects analysis and rad-hard design

Bring academic resources/expertise and real-world engineering to bear on system-driven needs

ISDE provides:

- Government and industry radiation-effects resource
  - Modeling and simulation
  - Design support: rad models, hardening by design
  - Technology support: assessment, characterization
- Flexible staffing driven by project needs
  - 10 Faculty
  - 25 Graduate students
  - 14 Staff and Research Engineers



# Schedule—May13 AM



8:40	MURI Overview
	Ron Schrimpf, Vanderbilt University
9:00	Overview: Atomic-Scale Theory of Radiation-Induced Phenomena
	Sokrates Pantelides, Vanderbilt University
9:20	Displacement Damage Effects in Single-Event Gate Rupture
	Matt Beck, Vanderbilt University
9:40	Role of Hydrogen in Aging of Electronics
	David Hughart and Sasha Batyrev, Vanderbilt University
10:00	Break
10:20	Effects of Aging and Moisture on 1/f Noise in MOS Devices
	Xing Zhou, Vanderbilt University
10:40	Defects in Non-Crystalline and Nano-Crystalline Alternative Transition Metal Dielectrics
	Gerry Lucovsky, North Carolina State University
11:00	Total Dose Response of Ge-substrate MOS Capacitors
	Rajan Arora, Vanderbilt University
11:20	Total Dose Effects on Ge pMOSFETs with High-k Gate Stacks: On–Off Current Ratio
	Shrinivasrao Kulkarni, Vanderbilt University

11:40 Lunch



# Schedule—May13 PM



- 12:40 Overview: Radiation Effects in Emerging Materials Len Feldman, Vanderbilt University
- 1:00 Interface Structure and Charge Trapping in HfO<sub>2</sub>-based MOSFETs Sriram Dixit, Vanderbilt University
- 1:20 Radiation Effects in Advanced Gate Stacks Eric Garfunkel, Rutgers University; Gennadi Bersuker, Sematech
- 2:00 Break
- 2:20 Total Dose and Single Event Effects in Strained Si Technologies Scott Thompson, University of Florida
- 2:40 Single-Event Transients in Strained-Si Devices Mark Law, University of Florida
- 3:00 Single-Event Transient Pulse-Width Measurements in Advanced Technologies Balaji Narasimham, Vanderbilt University
- 3:20 Assessing Alpha Particle-Induced Single Event Transient Vulnerability Matt Gadlage, Vanderbilt University
- 3:40 Analysis of Single-Event Latchup Cross-Section in 65 nm SRAMs John Hutson, Vanderbilt University
- 4:00 Overview: Monte Carlo Radiative Energy Deposition (MRED) Code Bob Weller, Vanderbilt University



### Schedule—May14



- 8:00 Registration and Continental Breakfast
- 8:30 Radiation Effects in SiGe Devices John Cressler, Georgia Tech
- 9:10 Radiation-Induced Current Transients in SiGe HBTs Jonathan Pellish, Vanderbilt University
- 9:30 Modeling Total Ionizing Dose Effects in Deep Submicron Bulk CMOS Technologies Hugh Barnaby, Arizona State University
- 9:50 Mechanisms of Enhanced Radiation-Induced Degradation due to Excess Molecular Hydrogen Jie Chen, Arizona State University
- 10:10 Break
- 10:30 Radiation Induced Leakage Current Enhancement in Irradiated Fully Depleted SOI Devices Farah El-Mamouni, Vanderbilt University
- 10:50 Single-Event Rate Prediction for Advanced Technologies Kevin Warren and Robert Reed, Vanderbilt University
- 11:10 Variation in Proton-Induced Energy Deposition in Large Silicon Diode Arrays Christina Howe, Vanderbilt University
- 11:30 Device-Orientation Effects on Single Event Upsets in 65-nm SRAMs Alan Tipton, Vanderbilt University
- 11:50 Meeting Ends

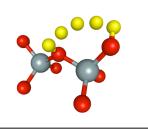


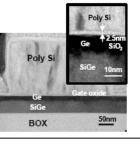
### Radiation Effects in Emerging Electronic Materials and Devices: Results



#### **Radiation Response of New Materials**

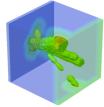
- Incorporation of new materials *dramatically* impacts radiation response
- HfO<sub>2</sub>-based dielectrics and emerging high-k materials tested; HfSiON is very promising
- Substrate engineering (strained Si, Si orientations, Si/SiGe, SOI, Ge substrates)

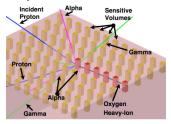




#### Single Events in New Technologies

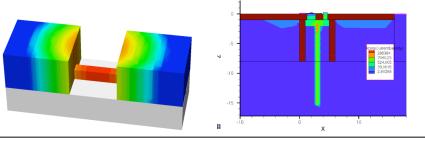
- RADSAFE—Most advanced Monte Carlo single-event/rateprediction tool
- Passivation/metallization found to *dominate* SEE response in some hardened technologies
- Excellent agreement with on-orbit data; conventional rateprediction methods underestimate rate by orders of magnitude





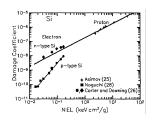
#### Impact of New Device Structures

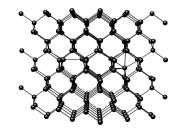
- New device technologies strongly impact single-event response and TID leakage current
- SiGe HBTs, strained Si CMOS, ultra-small bulk CMOS exhibit complicated charge collection mechanisms
- Floating-body SOI found to exhibit high radiation-induced off-state leakage due to tunneling



#### Localized Radiation Damage

- First-principles evidence of micro-melting in small devices
- Displaced atoms affect single-event dielectric rupture
- Monte-Carlo simulation tool for non-ionizing energy loss developed

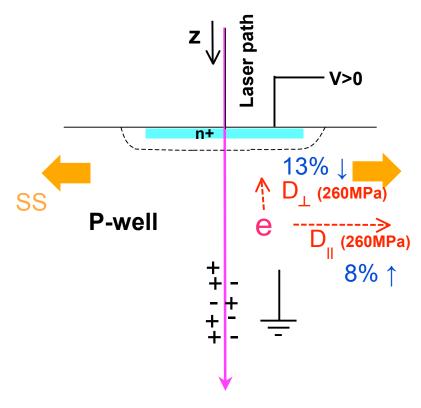




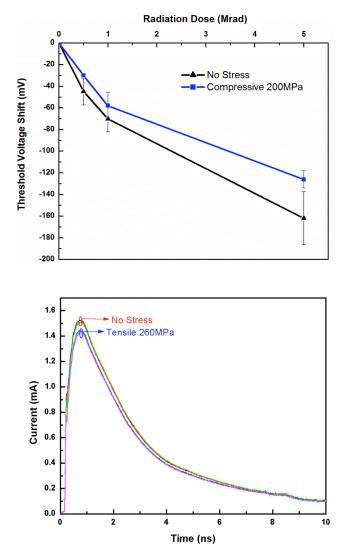


### Stress Effects on Radiation Response





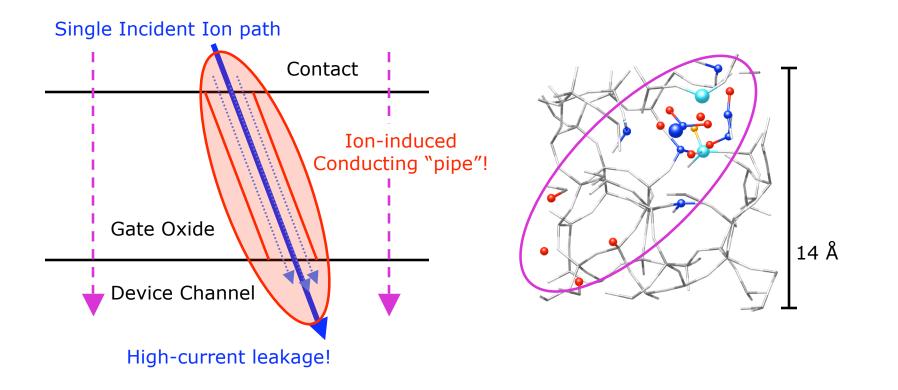
< 260 MPa Tensile Stress>





## Single-Event Dielectric Rupture

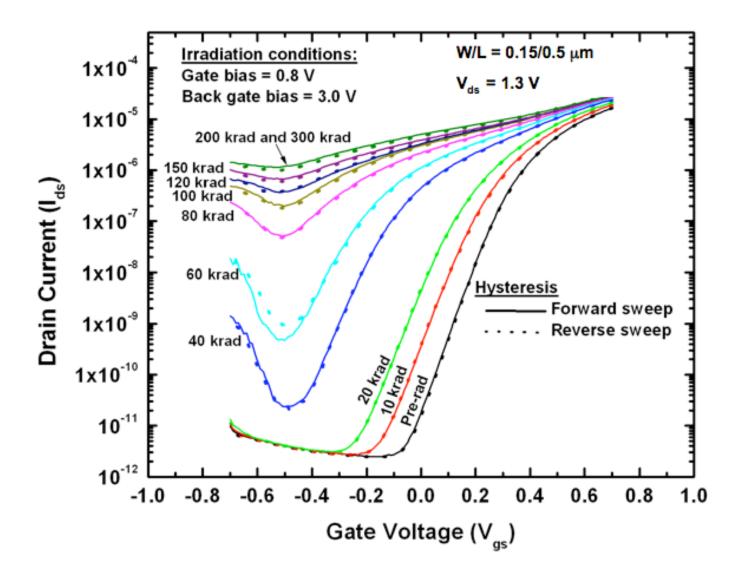






### **SOI Device Modeling**

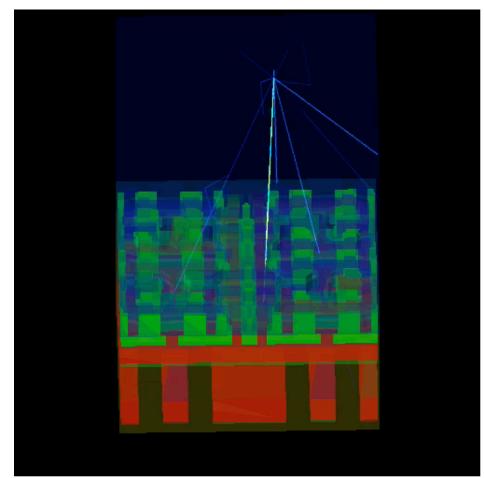






## **Energy Deposition Processes**





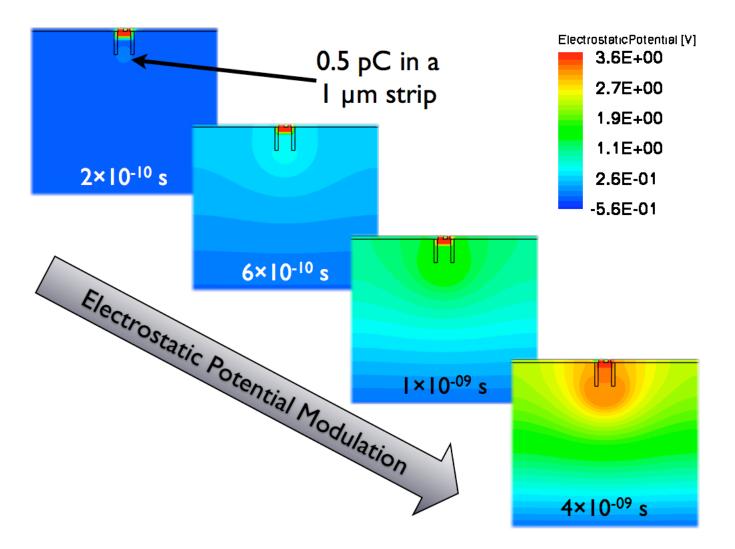


from Marcus Mendenhall



## **Charge Collection Mechanisms**

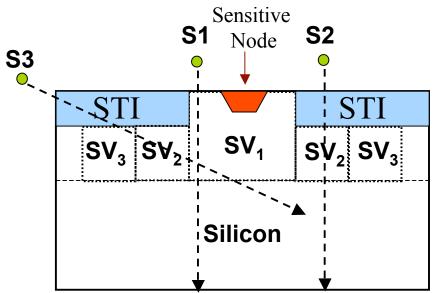


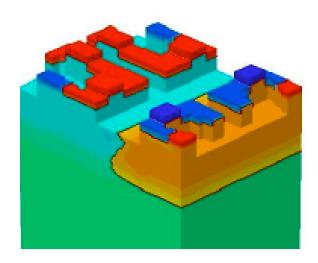


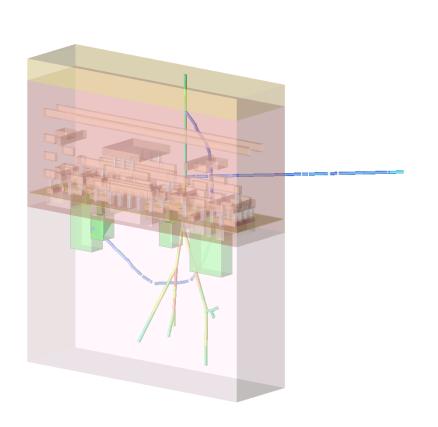


### **Advanced Rate Prediction**



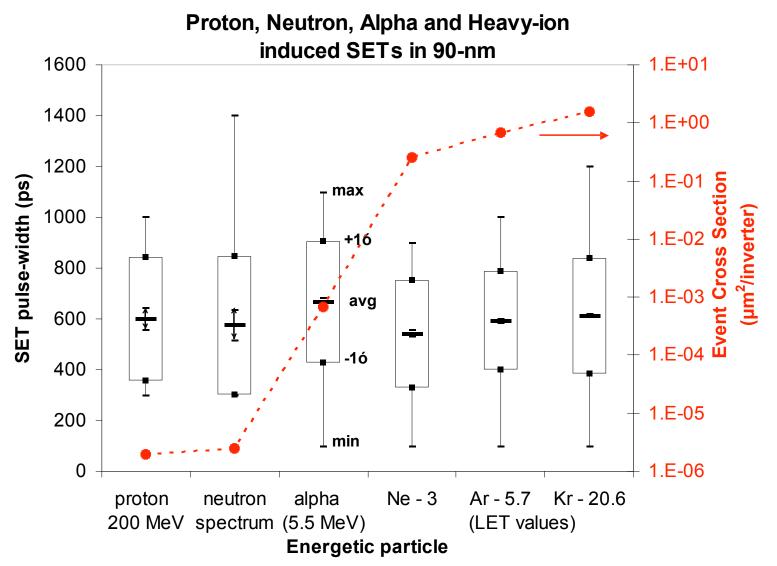








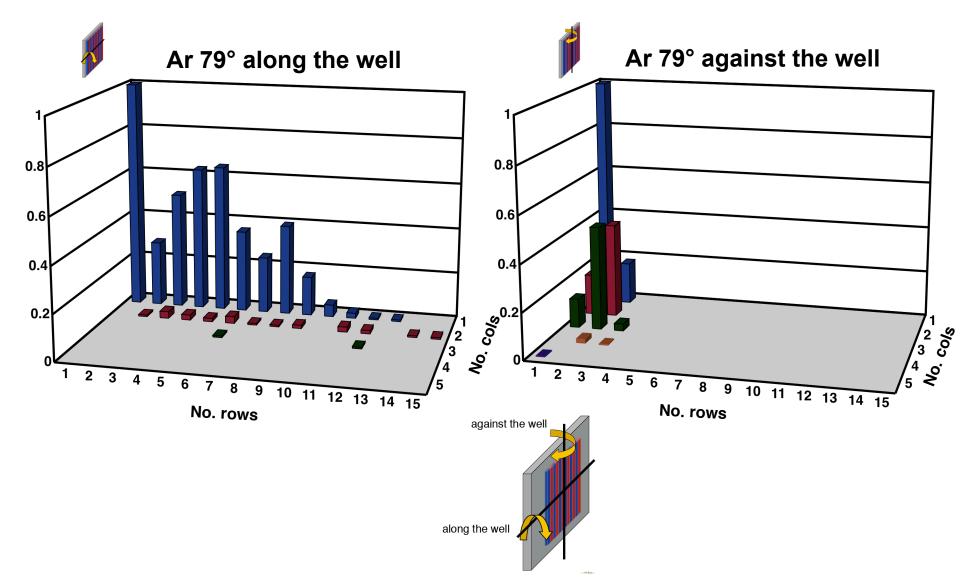






### Device Orientation Effects on Multiple-Bit Upset







### A few metrics...



- Personnel (2006-07)
  - 16 graduate students
  - 2 post-docs
  - 11 professors
- Publications
  - 51 appeared in print in 2006-07
  - 10 additional accepted